



Optimizing Test Cell Performance

20th 2-0-1-0
ANNIVERSARY

Rey Rincon
Freescale Semiconductor

John Strom, Jeff Greenberg
Rudolph Technologies

RUDOLPH
TECHNOLOGIES



June 6 to 9, 2010

IEEE SW Test Workshop

1

Problem Statement

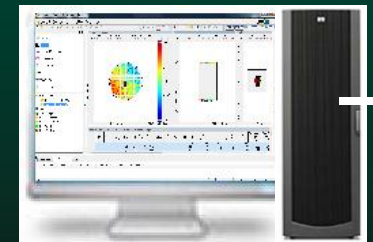
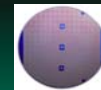
- **How are we going to optimize Test Cell performance?**
 - Investigate Prober performance
 - Investigate Probe Card performance
 - Investigate Probe Card Analyzer correlation to Test Cell



Design Of Experiment

- **Pass1**

- Measure/Adjust probe card on PrecisionPoint® VX3
- Probe wafers
- Inspect probe marks with NSX® after probing
- Measure Probing Process performance with WaferWoRx® on NSX
- Compute VX3 correlation to scrub marks



PMI data



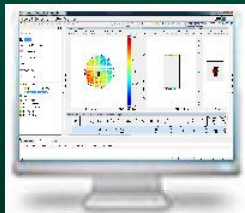
June 6 to 9, 2010

IEEE SW Test Workshop

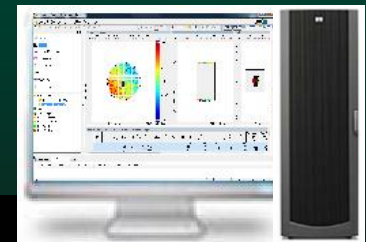
Design Of Experiment

- **Pass2**

- Adjust Probe Card on PrecisionWoRx® VX4 using “*Predictive Scrub*”
- Probe wafers
- Inspect probe marks with NSX after probing
- Measure Probing Process performance improvements with WaferWoRx on NSX



Pass1 WWX info



PMI data

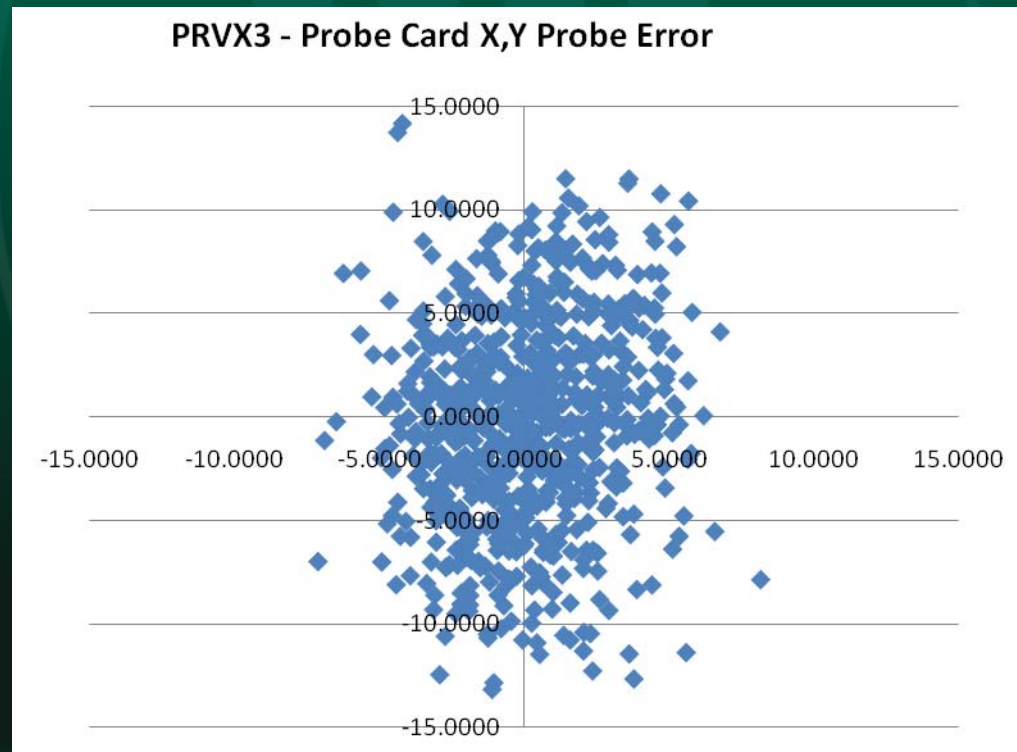


June 6 to 9, 2010

IEEE SW Test Workshop

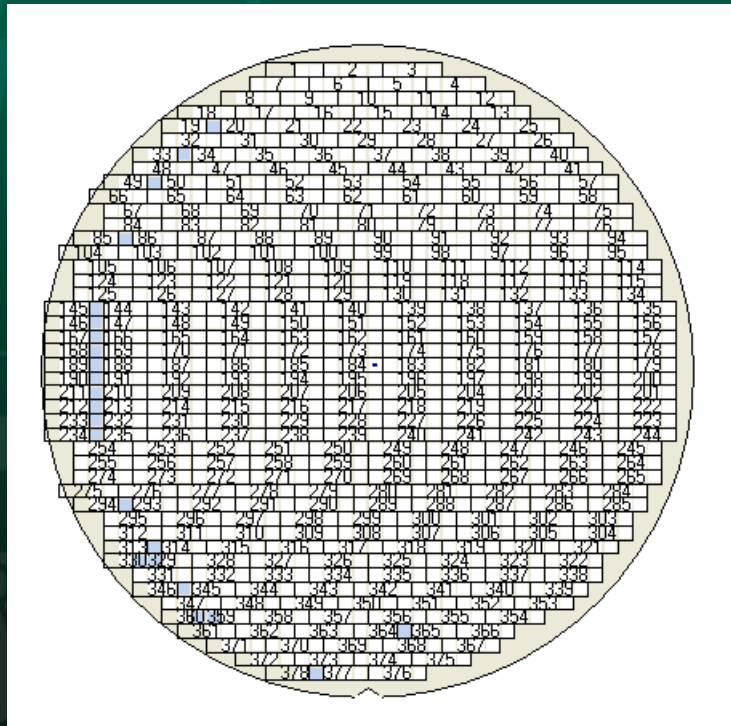
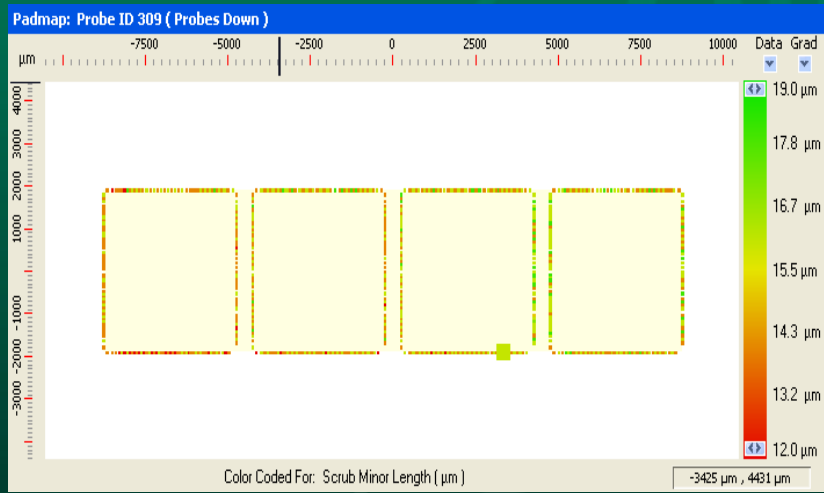
Pass1: Measure/Adjust probe card on VX3

- VX3 data shows probe's center of scrub is within spec and nominally centered on the pad



Pass1: Probe Wafers

- 200mm wafer
- 378 Touchdowns



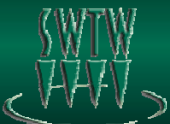
- Cantilever probe card (4 X 1)
- 700+ probes
- Two tiers (different tip lengths)¹

Strom, "Multi-tier Probe Cards and Contact Resistance, SWTW 1998"¹
Strom, A Study of Probing Process Analysis, SWTW 1999¹



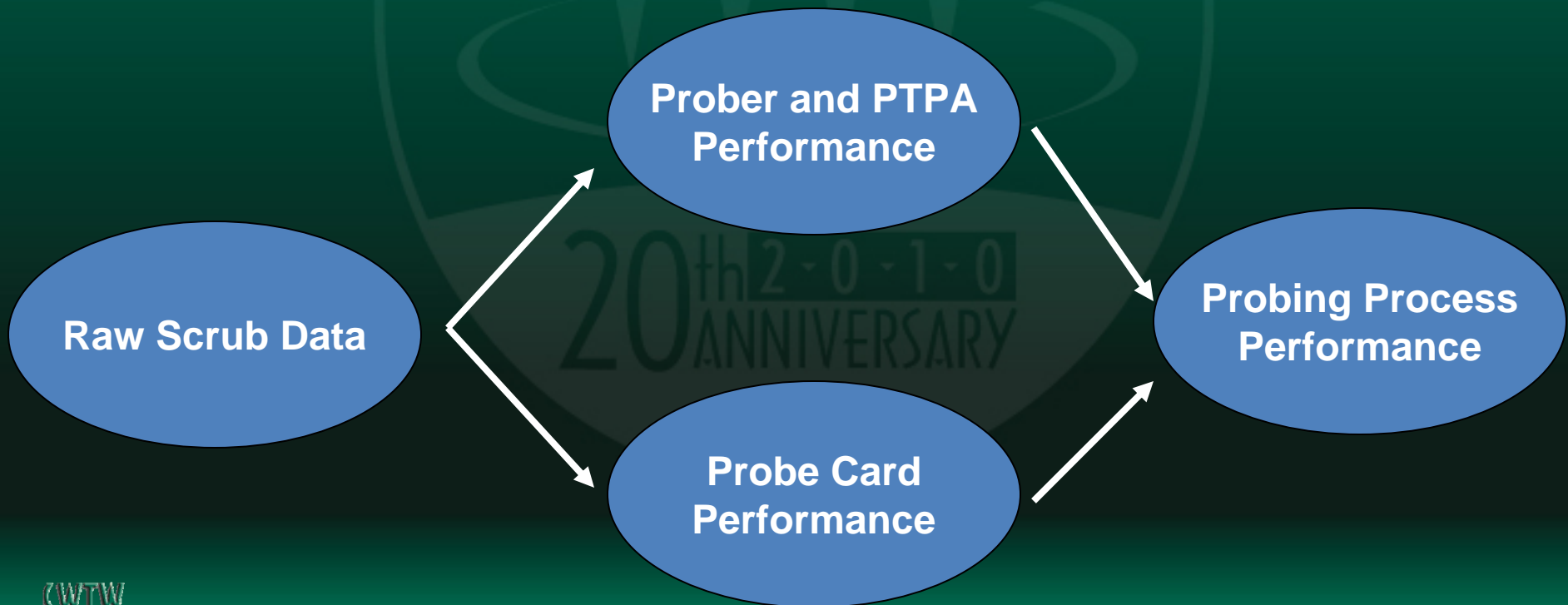
Pass1: PMI Results

Results Table																				
Index	Die Column	Die Row	Die ID	Pad ID	Scrub ID	Probe ID	DUT ID	Scrub X Size (µm) ✓	Scrub Y Size (µm) ✓	Scrub X Pos (µm) ✓	Scrub Y Pos (µm) ✓	Scrub Minor Length (µm) ✓	Scrub Major Length (µm) ✓	Scrub Angle (°) ✓	Scrub Align (µm) ✓	Edge Distance (µm) ✓	Left Distance (µm) ✓	Right Distance (µm) ✓	Top Distance (µm) ✓	Bottom Distance (µm) ✓
1																				
2																				
3																				
4																				
5																				
6																				
7																				
8																				
9																				
10																				
11																				
12																				
13																				
14																				
15																				
16																				
17																				
18	10	0	-1	1	10	1	10	1	10	1	10	1	10	1	10	1	10	1	10	1
19	11	0	-1	1	11	1	11	1	11	1	11	1	11	1	11	1	11	1	11	1
20	12	0	-1	1	12	1	12	1	12	1	12	1	12	1	12	1	12	1	12	1
21	13	0	-1	1	13	1	13	1	13	1	13	1	13	1	13	1	13	1	13	1
22	14	0	-1	1	14	1	14	1	14	1	14	1	14	1	14	1	14	1	14	1
23	15	0	-1	1	15	1	15	1	15	1	15	1	15	1	15	1	15	1	15	1
24	16	0	-1	1	16	1	16	1	16	1	16	1	16	1	16	1	16	1	16	1
25	17	0	-1	1	17	1	17	1	17	1	17	1	17	1	17	1	17	1	17	1
26	18	0	-1	1	18	1	18	1	18	1	18	1	18	1	18	1	18	1	18	1
27	19	0	-1	1	19	1	19	1	19	1	19	1	19	1	19	1	19	1	19	1
28	20	0	-1	1	20	1	20	1	20	1	20	1	20	1	20	1	20	1	20	1
29	21	0	-1	1	21	1	21	1	21	1	21	1	21	1	21	1	21	1	21	1
30	22	0	-1	1	22	1	22	1	22	1	22	1	22	1	22	1	22	1	22	1
31	23	0	-1	1	23	1	23	1	23	1	23	1	23	1	23	1	23	1	23	1
32	24	0	-1	1	24	1	24	1	24	1	24	1	24	1	24	1	24	1	24	1
33	25	0	-1	1	25	1	25	1	25	1	25	1	25	1	25	1	25	1	25	1
34	26	0	-1	1	26	1	26	1	26	1	26	1	26	1	26	1	26	1	26	1
35	27	0	-1	1	27	1	27	1	27	1	27	1	27	1	27	1	27	1	27	1
36	28	0	-1	1	28	1	28	1	28	1	28	1	28	1	28	1	28	1	28	1
37	29	0	-1	1	29	1	29	1	29	1	29	1	29	1	29	1	29	1	29	1
38	30	0	-1	1	30	1	30	1	30	1	30	1	30	1	30	1	30	1	30	1
39	31	0	-1	1	31	1	31	1	31	1	31	1	31	1	31	1	31	1	31	1
40	32	0	-1	1	32	1	32	1	32	1	32	1	32	1	32	1	32	1	32	1
41	33	0	-1	1	33	1	33	1	33	1	33	1	33	1	33	1	33	1	33	1
42	34	0	-1	1	34	1	34	1	34	1	34	1	34	1	34	1	34	1	34	1

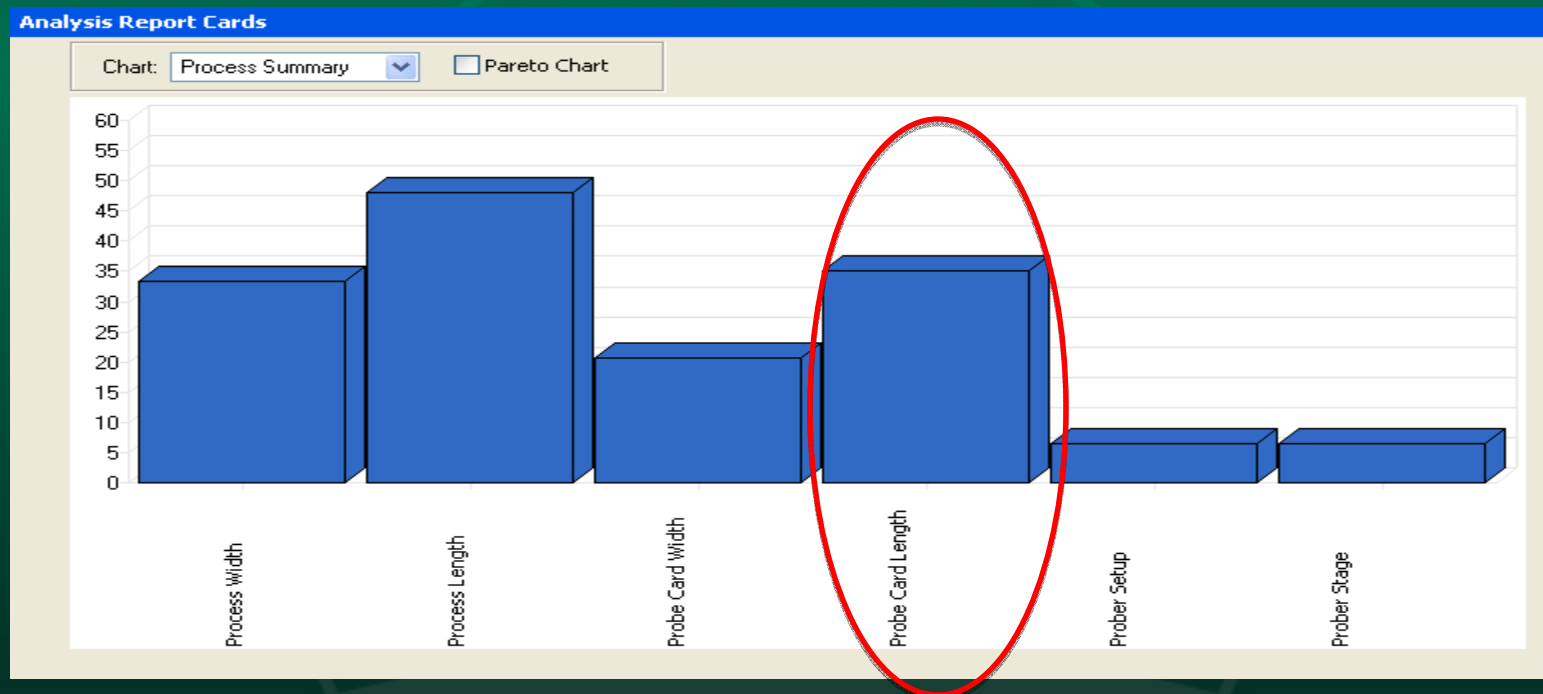


Pass1: Probing Process Analysis Overview

- PMI raw scrub mark data is input
- Prober, Probe to Pad Alignment (PTPA) and Probe Card performance is calculated
- Process performance is determined from combined Prober and Probe Card performance



Pass1: Probing Process Performance Summary

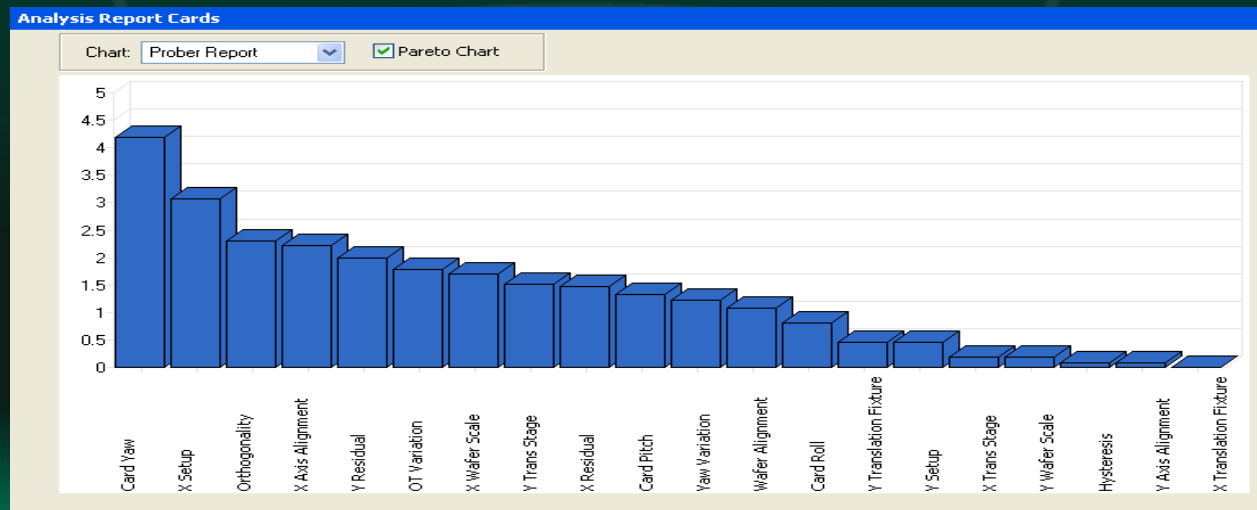


- Process Length issues
 - Pad Size = 60 microns and the Process Length = 48 microns
 - Single Wafer CPK ~ 1.25
- Probe Card is the major error source
- Prober error contribution relatively small compared to Probe Card error

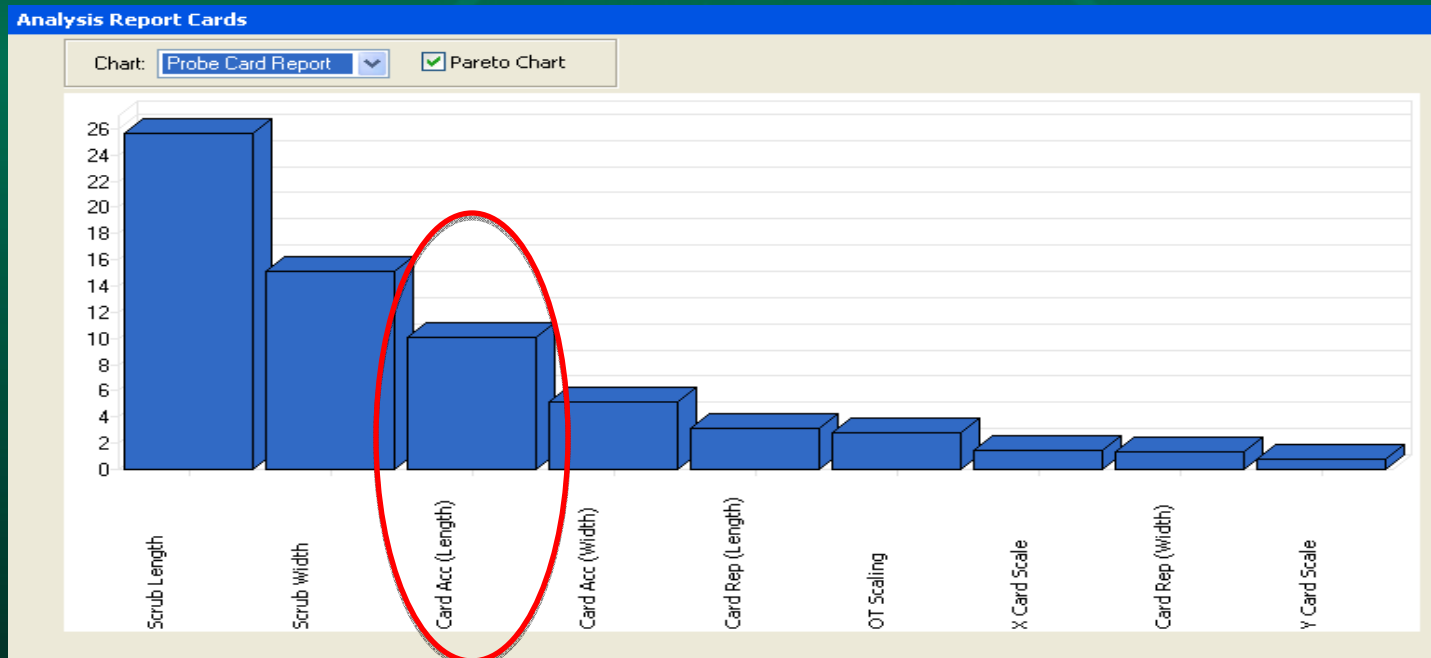


Pass1: Prober Performance Summary

- Overall prober error \approx 12 microns
- Probe to Pad Alignment larger than normal (\sim 5 microns)
- Deflection/Translation under load relatively large for just 800 pins – may be problematic with higher load probe cards
- Small Orthogonality and Scaling errors in stage motion



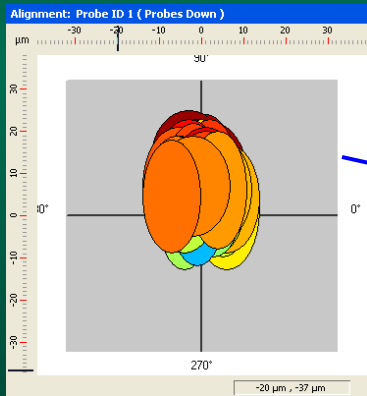
Pass1: Probe Card Performance



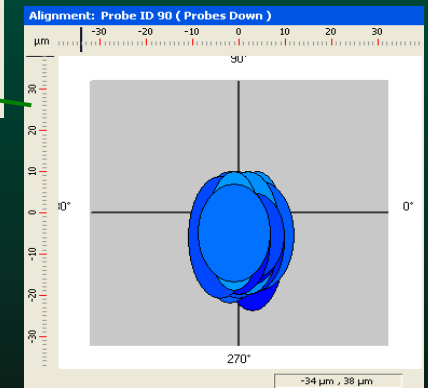
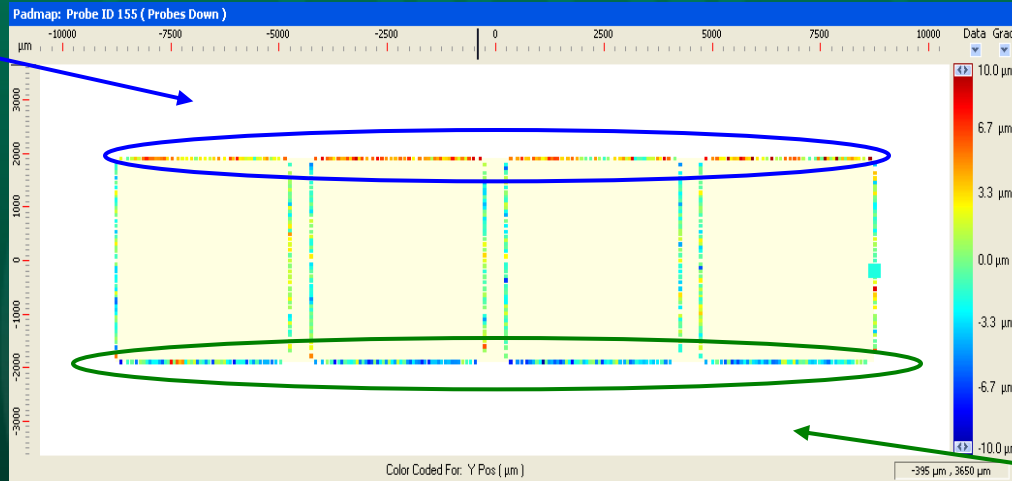
- No XY scaling errors
- Good repeatability
- Scrub Length and Width typical for a cantilever probe card
- Probe Card Length Accuracy is the major error source (10 microns)



Pass1: Probe Card SuperPad View



Top row only

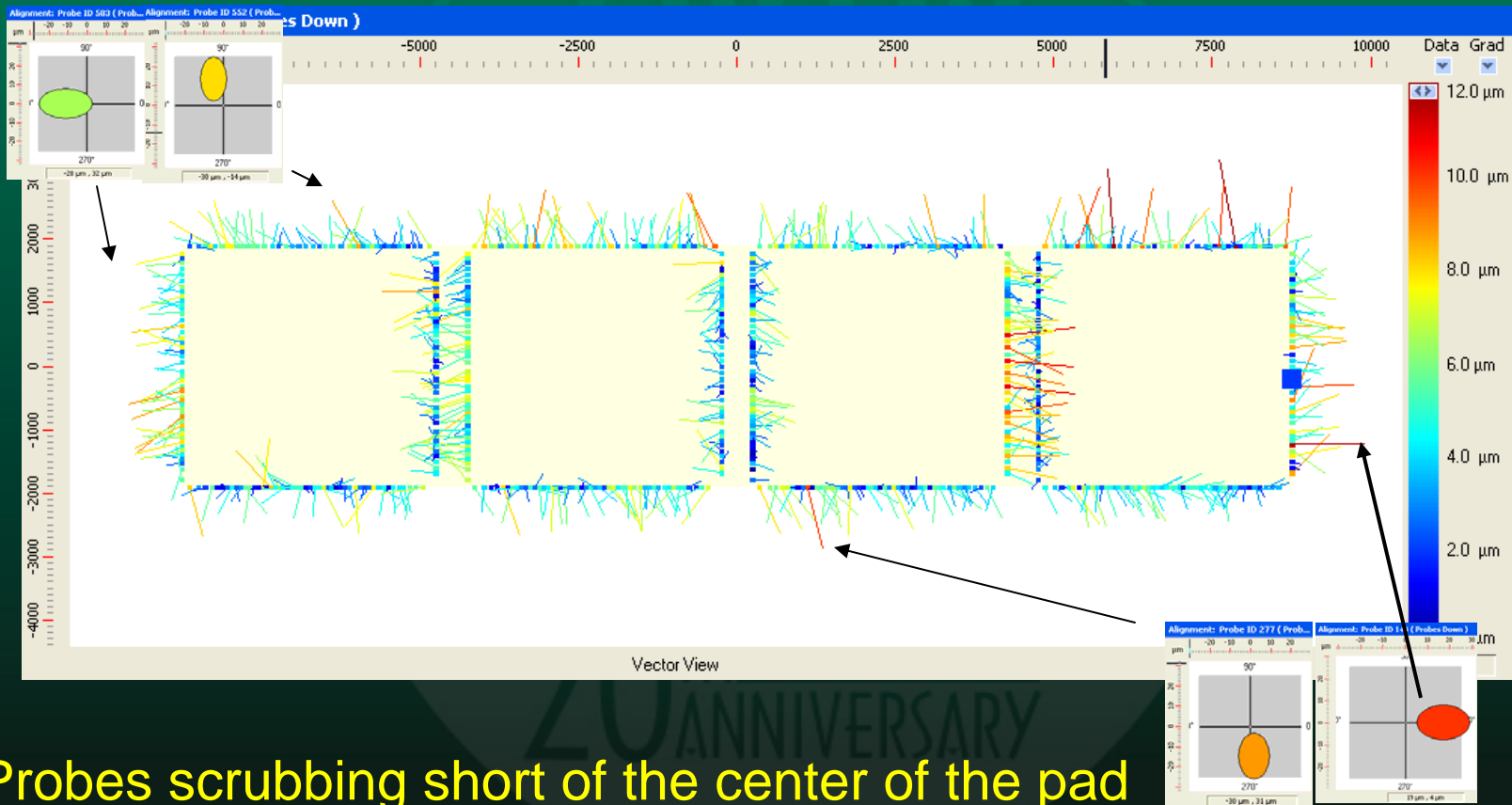


Bottom row only

- Probes are scrubbing short of pad center
- Different tiers have different offsets



Pass1: Probe Card Vector View Of Alignment Errors



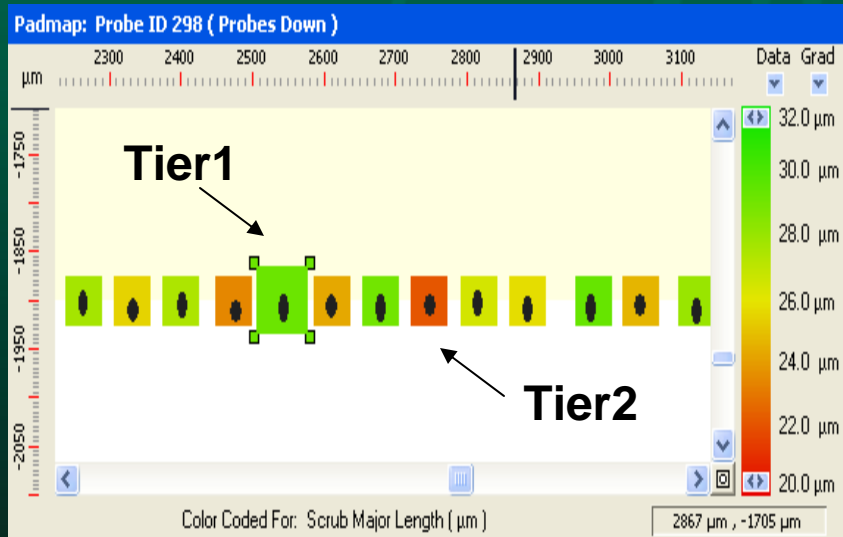
- Probes scrubbing short of the center of the pad
- Tiers have different errors / scrub characteristics

Vector pointing to the right = scrub center is to the right of pad center.

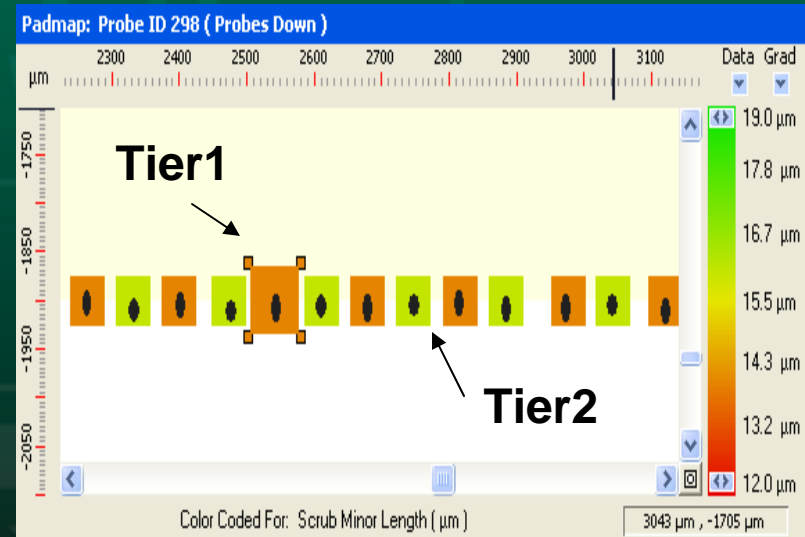


Pass1: Probe Card Scrub Length and Scrub Width

Color Coded for Scrub Length



Color Coded for Scrub Width

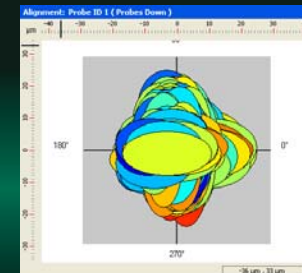


- Interleaved tiers have different scrub characteristics
 - Tier1: Shorter tip lengths = long and thin scrubs
 - Tier2: Longer tip lengths = short and wide scrubs



Pass1: Probe Card Performance Summary

- **Pros**
 - Probe positions show no XY scaling error
 - Probes positions (scrub marks) are repeatable
- **Cons**
 - Probes are scrubbing short of the pad center
 - Multiple tiers/tip lengths each have different scrub characteristics
 - Long Tip Length: Short wider scrub
 - Short Tip Length: Long thin scrub
 - Can not resolve by simply changing overtravel
- **Probe card performance problems consume major part of pad**



Probe Card Analyzer to Test Cell Correlation Analysis



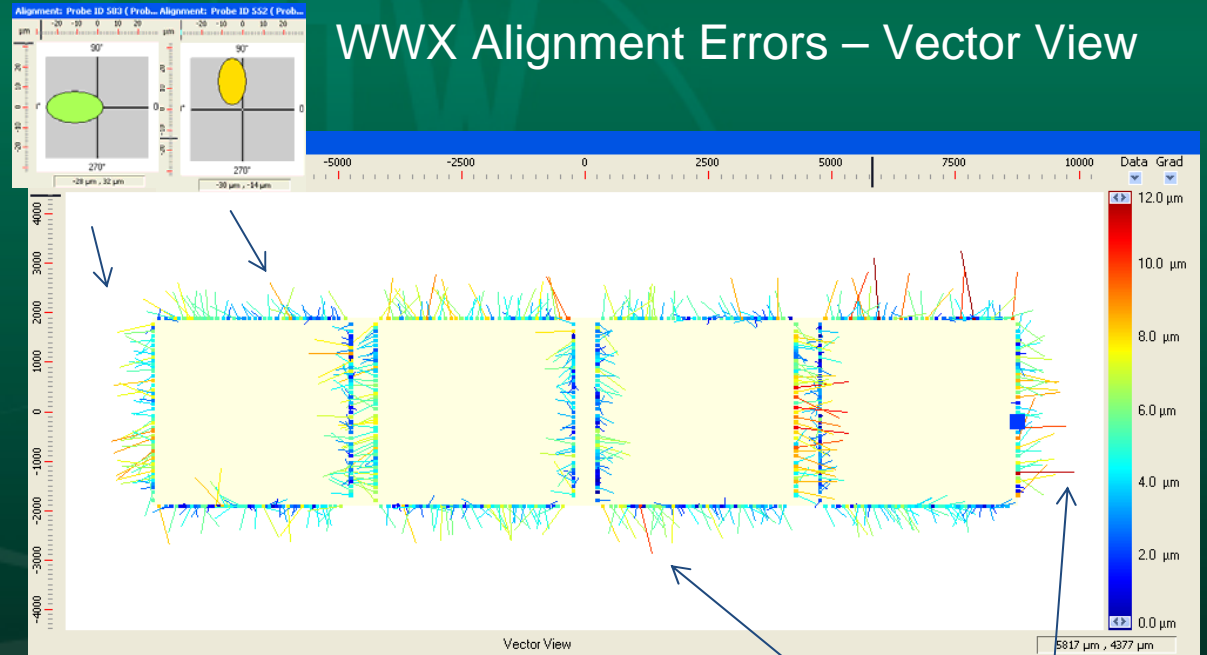
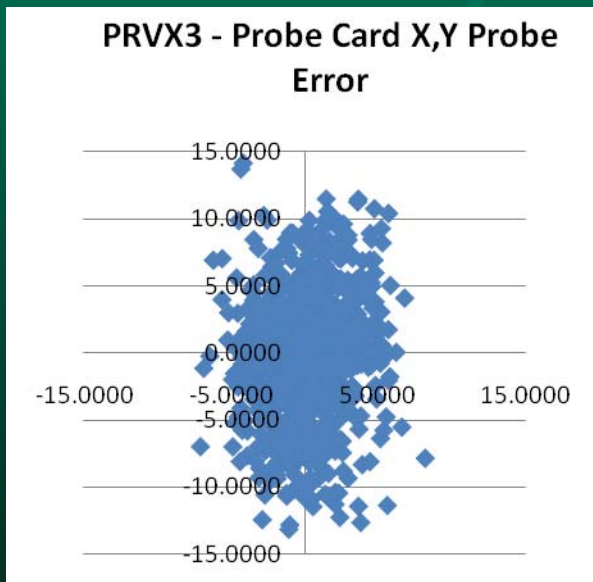
June 6 to 9, 2010

IEEE SW Test Workshop

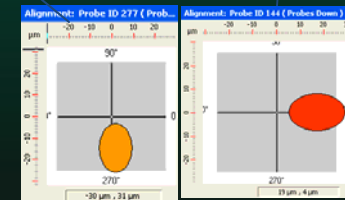
16

Pass1: Test Cell vs. VX3 Probe Card Correlation

VX3



- VX3 measures probe center of scrub ≈ center of pad
- WaferWoRx shows probes scrubbing short of pad center

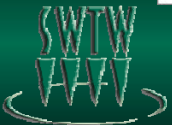
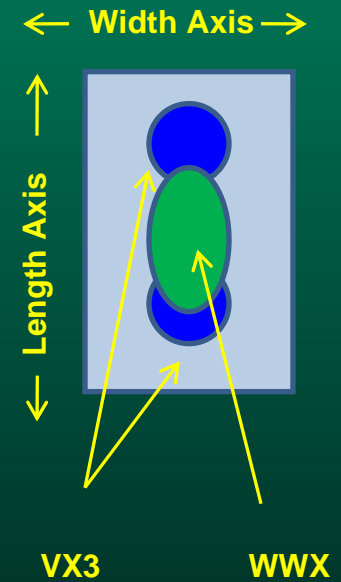
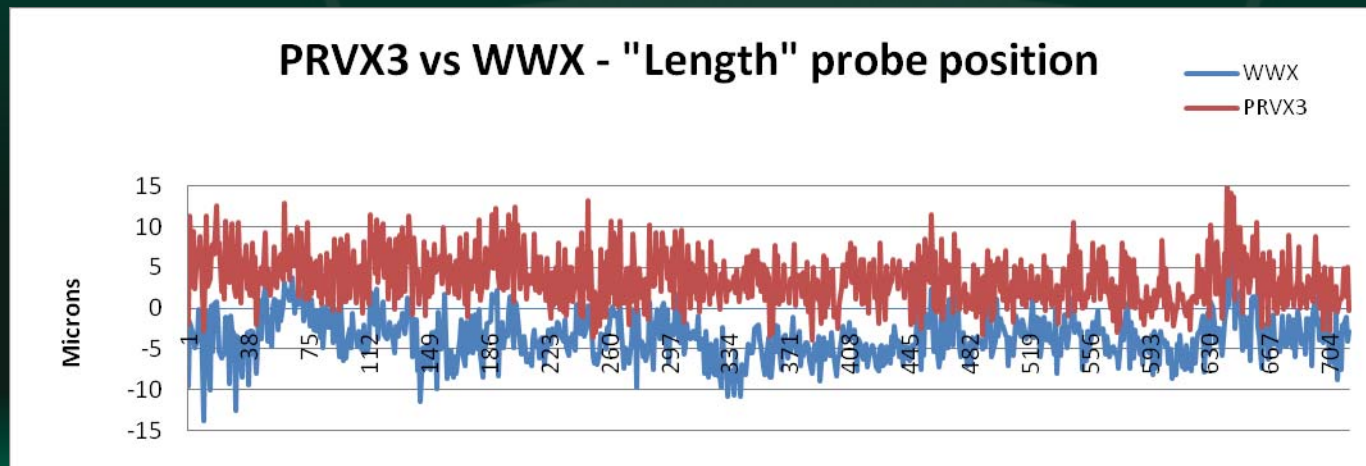
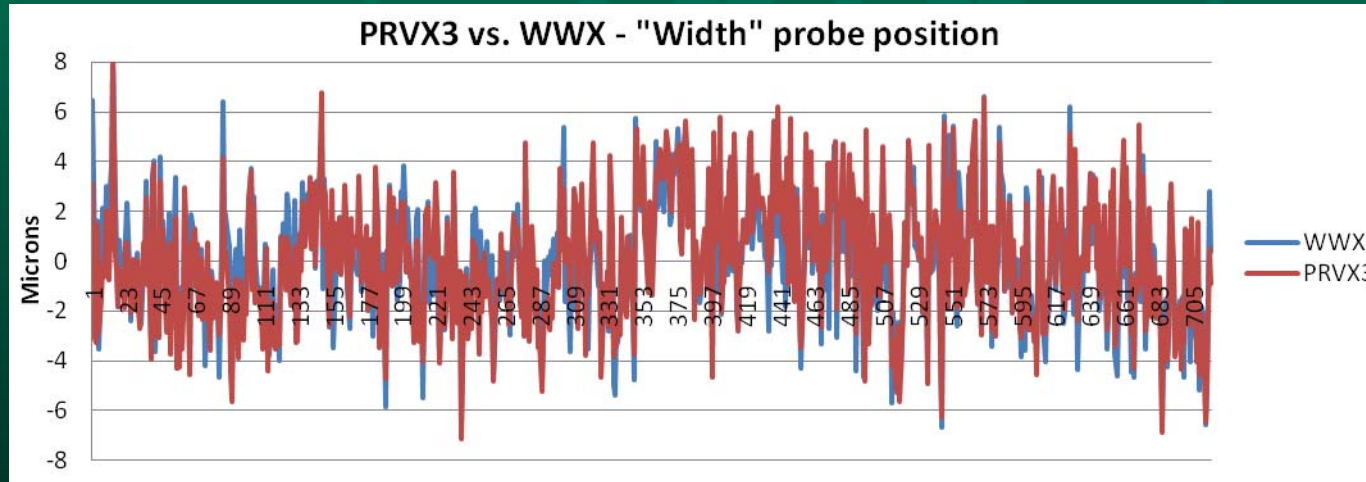


Vector pointing to the right = scrub center is to the right of pad center



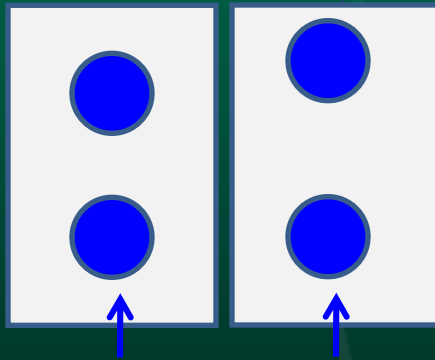
Pass1: Test Cell vs. VX3 Probe Position – Absolute

Probe Relative analysis



Review Cantilever Probe Scrub Properties on PCA Measurement Window vs. on Bond Pad

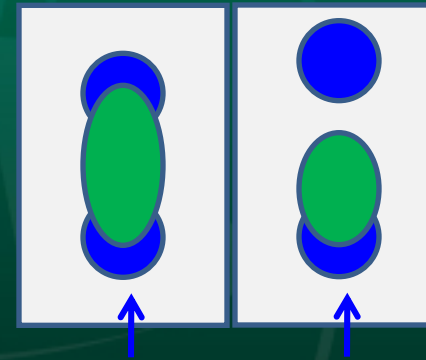
Short tip length Long tip length



PCA Window – Low Friction

- Minimal probe tip deflection because friction is low
- Scrub length increases with tip length

Short tip length Long tip length

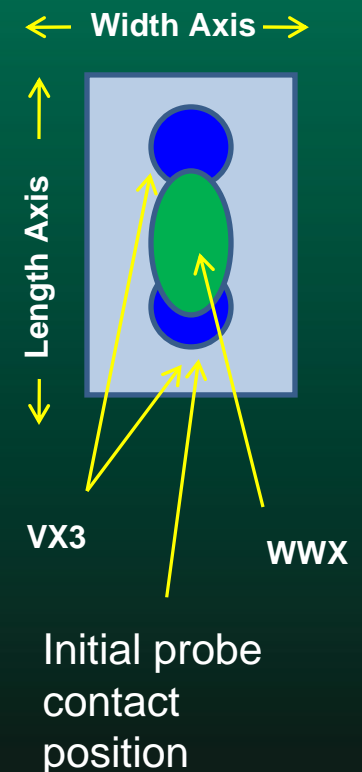


Aluminum Bond Pad – High Friction

- Significant probe tip deflection because friction is high
- Longer tip lengths scrub shorter due to higher deflection
- Shorter tip lengths scrub longer due to lower deflection

Pass1: Test Cell to VX3 Correlation - Summary

- Good correlation in “Width” axis between VX3 and WaferWoRx data
 - VX3 is accurately representing the initial contact position of the probe
- Correlation issue in the “Length” axis
 - Losing ~ 10 microns of scrub position due to cantilever probe scrub characteristic differences on hard surface vs. aluminized pad



Process Improvement Opportunities

Prober Improvement

- Probe to Pad Alignment Improvements (Yaw and X Offset)
 - Process improvement available ~5 microns

Probe Card Improvement

- Use VX4 “Predictive Scrub” during card adjustment
 - Process improvement available ~10 microns





“Predictive Scrub”



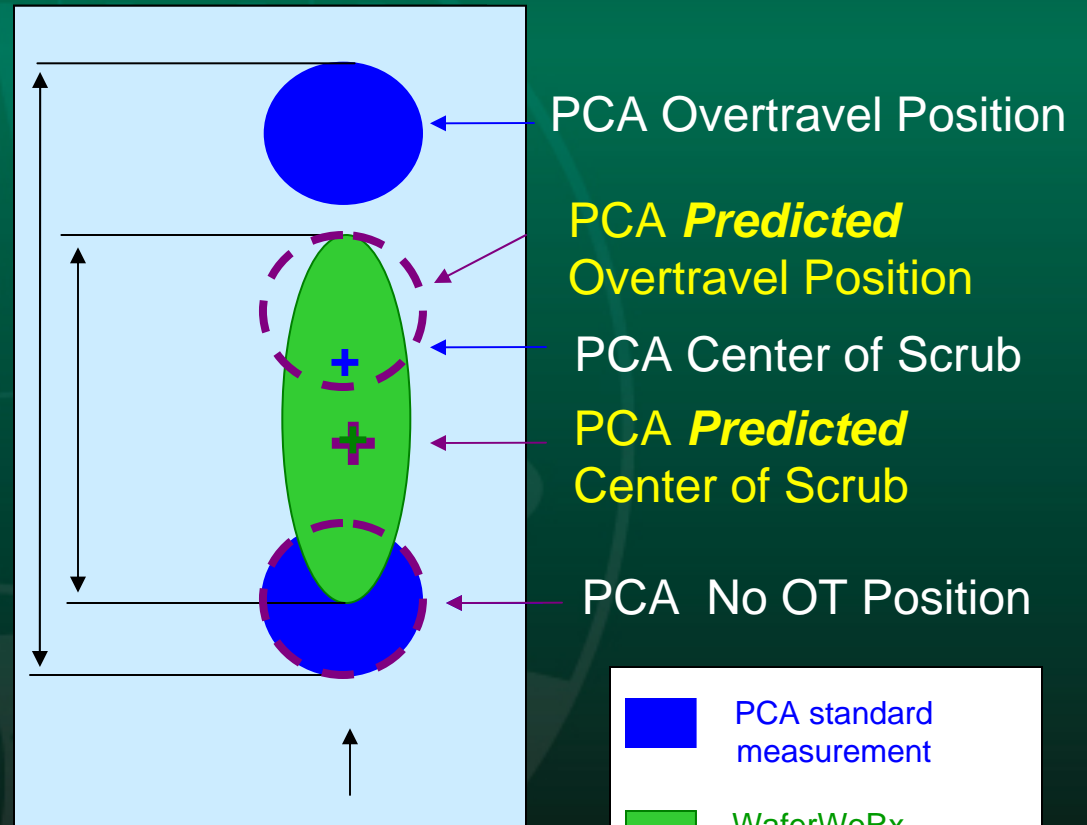
June 6 to 9, 2010

IEEE SW Test Workshop

22

Predictive Scrub

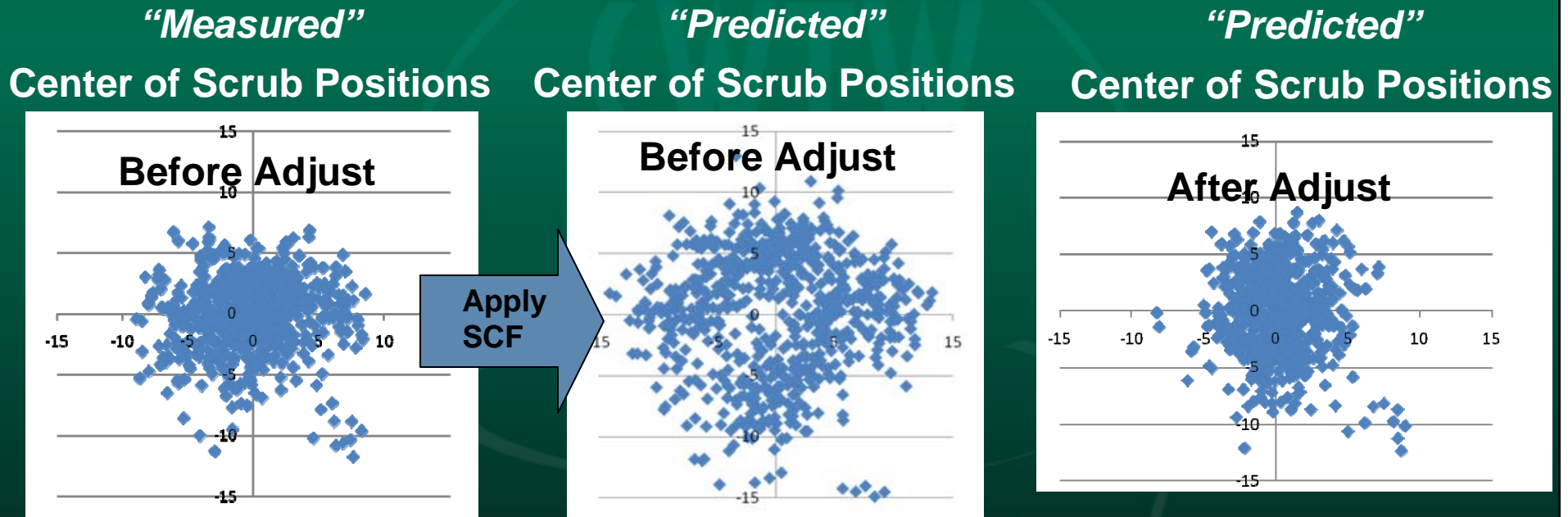
- 1) PCA measurement
- 2) WaferWoRx Probe Card measurement from PMI data
- 3) Quantify differences between PCA and Test Cell
- 4) Measure **Predictive Scrub** with VX4



■	PCA standard measurement
■	WaferWoRx measurement
■	PCA Predicted Scrub Measurement

	Probe ID	Channel Label	User Defined Label 1	User Defined Label 2	X Reference (μm)	Y Reference (μm)	Major Diameter (μm)	Minor Diameter (μm)	Tier	Probe Scrub Correlation
1	1	1015	472	0_001	-1894.000	8647.660	20.000	20.000	1	0.80
2	2	MC2	329	0_002	-1894.000	8497.580	20.000	20.000	2	0.60
3	3	354	200	0_003	-1894.000	8397.340	20.000	20.000	1	0.80
4	4	351	201	0_006	-1894.000	8315.860	20.000	20.000	2	0.60
5	5	489	344	0_007	-1894.000	8235.500	20.000	20.000	1	0.80
6	6	459	330	0_008	-1894.000	8159.060	20.000	20.000	2	0.60
7	7	1018	456	0_009	-1894.000	8083.180	20.000	20.000	1	0.80
8	8	490	328	0_010	-1894.000	8011.220	20.000	20.000	2	0.60
9	9	551	198	0_011	-1894.000	7938.700	20.000	20.000	1	0.80
10	10	458	346	0_012	-1894.000	7868.700	20.000	20.000	2	0.60

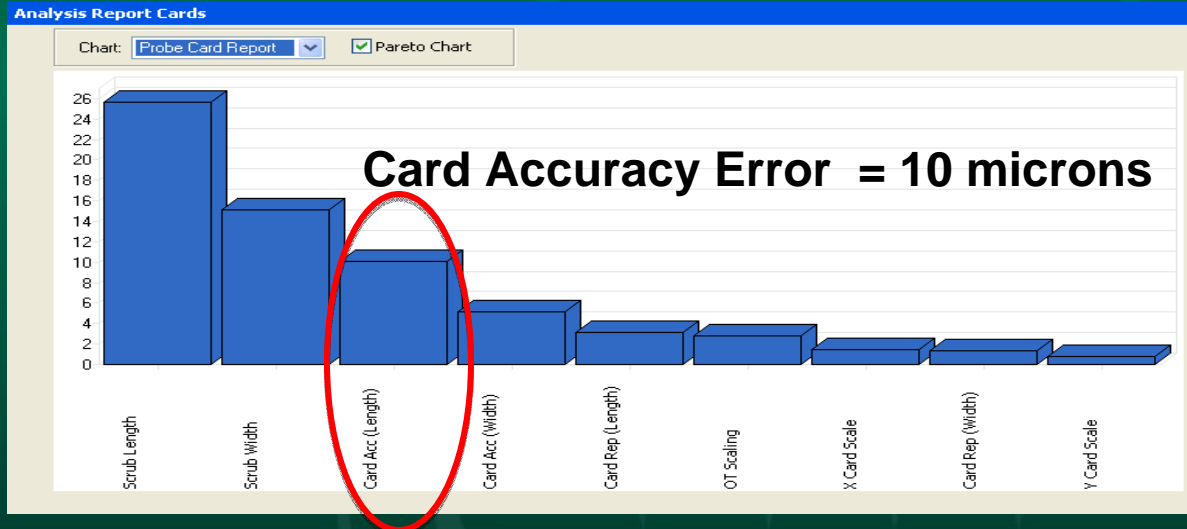
Pass 2: Measure Probe Card on VX4 Before and After Adjust



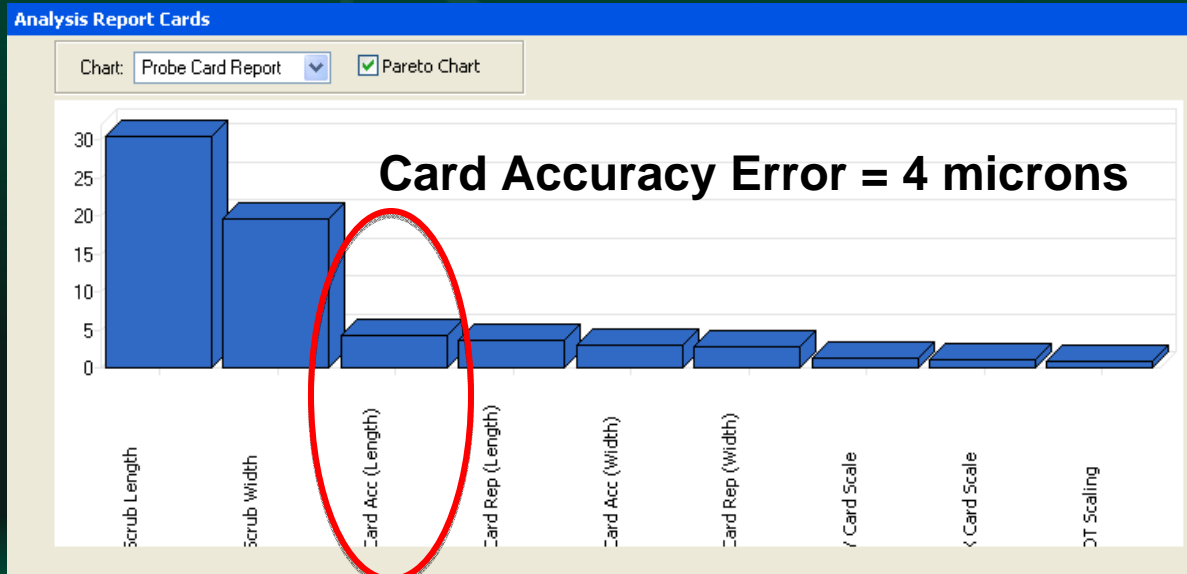
- VX4 Results **BEFORE** adjusting probe positions
 - Measured positions are well centered
 - Predicted positions have a donut hole of probes scrubbing short of center
- VX4 Results **AFTER** adjusting probe positions based on Predicted Positions
 - Predicted positions are now well centered



Pass 2: Measure Process Improvements



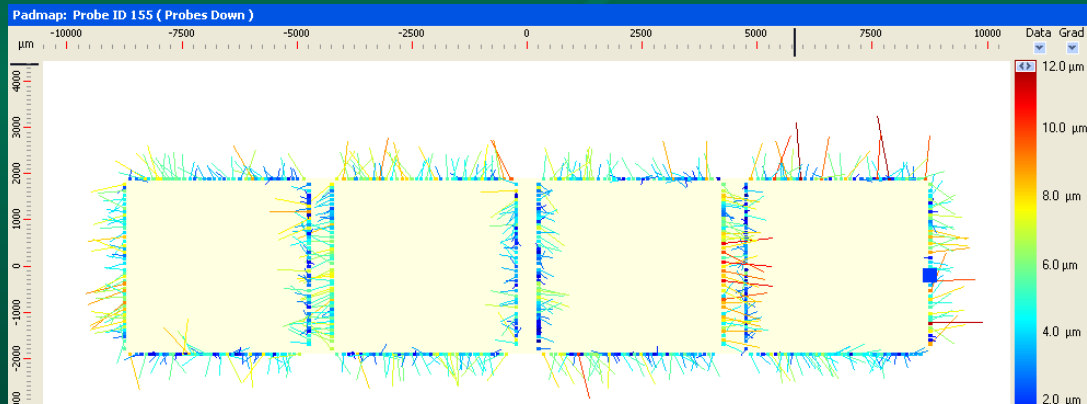
Pass1 Results



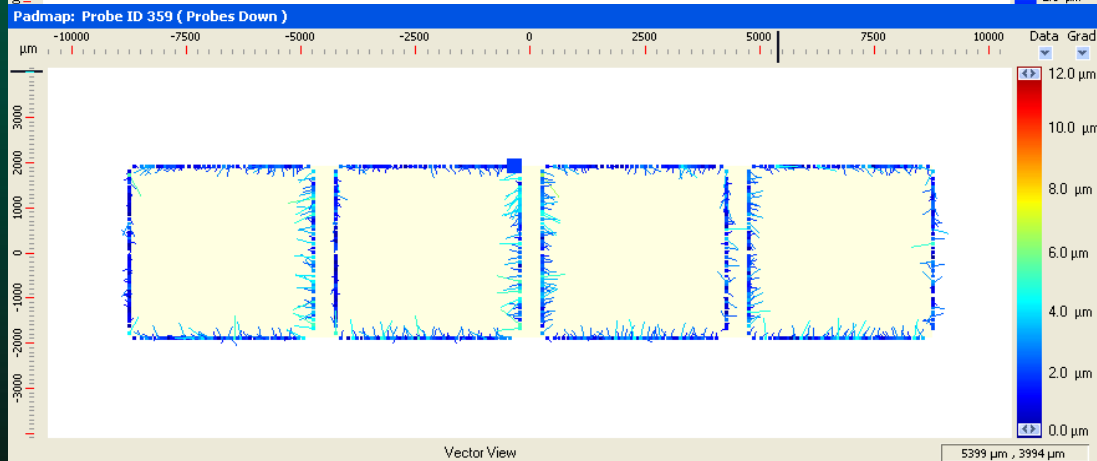
Pass2 Results



Pass 2: Probe Card Performance Details



Pass1 WaferWoRx Results



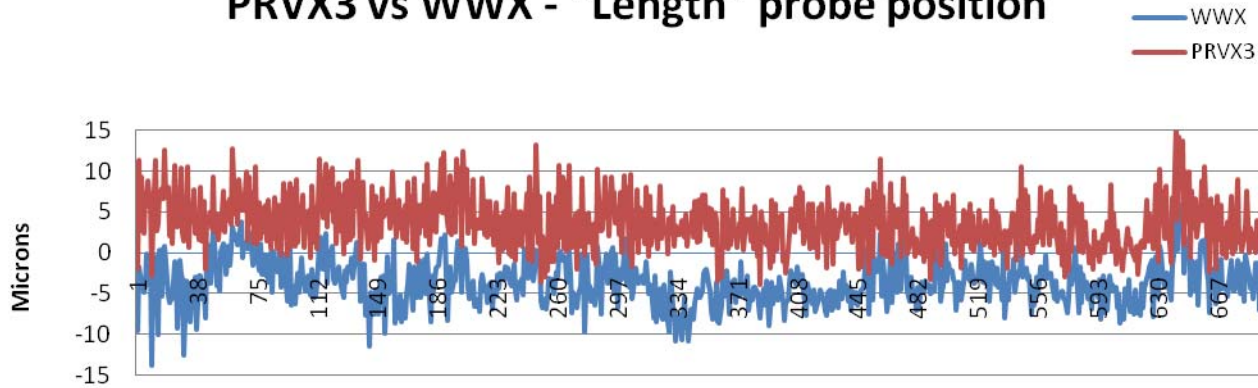
Pass2 WaferWoRx Results

- Probes scrubbing short of pad center for Pass1 data
- Probes are well centered for Pass2 data
 - Probe Card was adjusted using VX4 *“Predictive Scrub”*



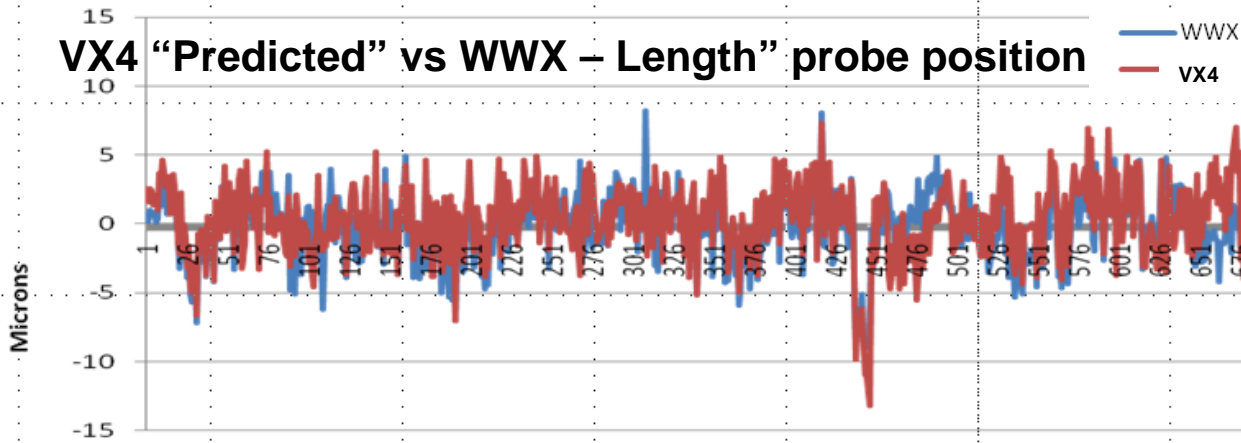
Pass 2: VX4 "Predictive Scrub" Correlation to Test Cell

PRVX3 vs WWX - "Length" probe position



Pass1
Correlation

VX4 "Predicted" vs WWX - "Length" probe position



Pass2
Correlation



Summary

- **We were able to improve Test Cell performance!**
- **CPK improvements**
 - Pass1 CPK = 1.25, Process Length = 48 microns
 - Pass2 CPK = 1.45, Process Length = 41.3 microns
- **Probe Card Performance improvements by adjusting probe positions based on VX4 “Predictive Scrub”**
 - Pass1 Length Accuracy Error = 10 microns
 - Pass2 Length Accuracy Error = 4 microns
- **Improved Probe Card Analyzer correlation to Test Cell using VX4 “Predictive Scrub”**
- **Identified Prober Stage and PTPA Errors with WaferWoRx on NSX Probing Process Analysis**
 - Additional performance improvement available to pursue



Acknowledgements

Freescale Semiconductor

John Vanderbilt, Greg Faulkner, Devin Sheridan

Rudolph Technologies

Darren James, Rod Doe, WooYoung Han

JEM

Patrick Mui

Other Contributors

Fred Megna, Kajiwara “Kaji” Kunitomo

